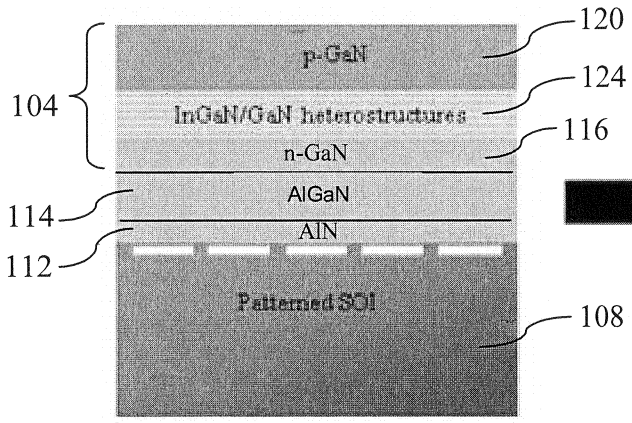


FIG. 1A

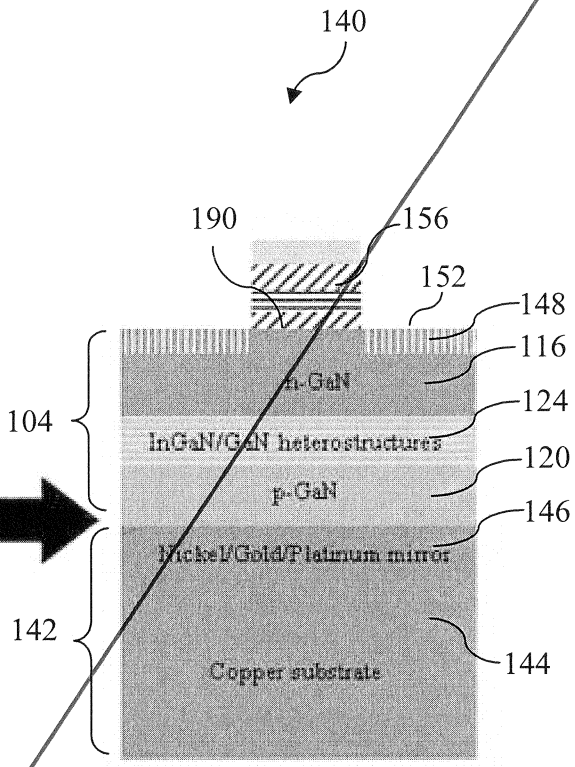


FIG. 1B

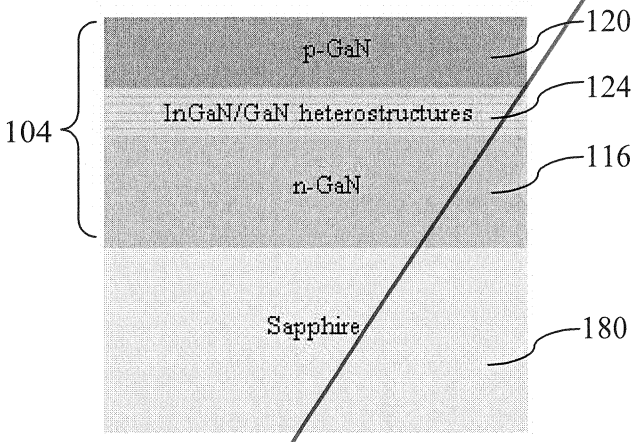


FIG. 1C

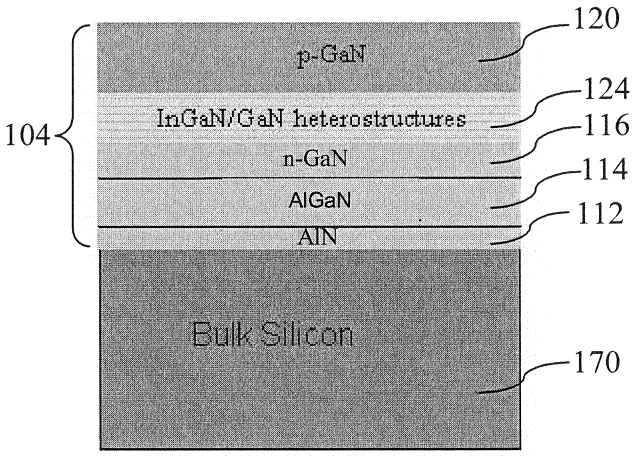


FIG. 1D

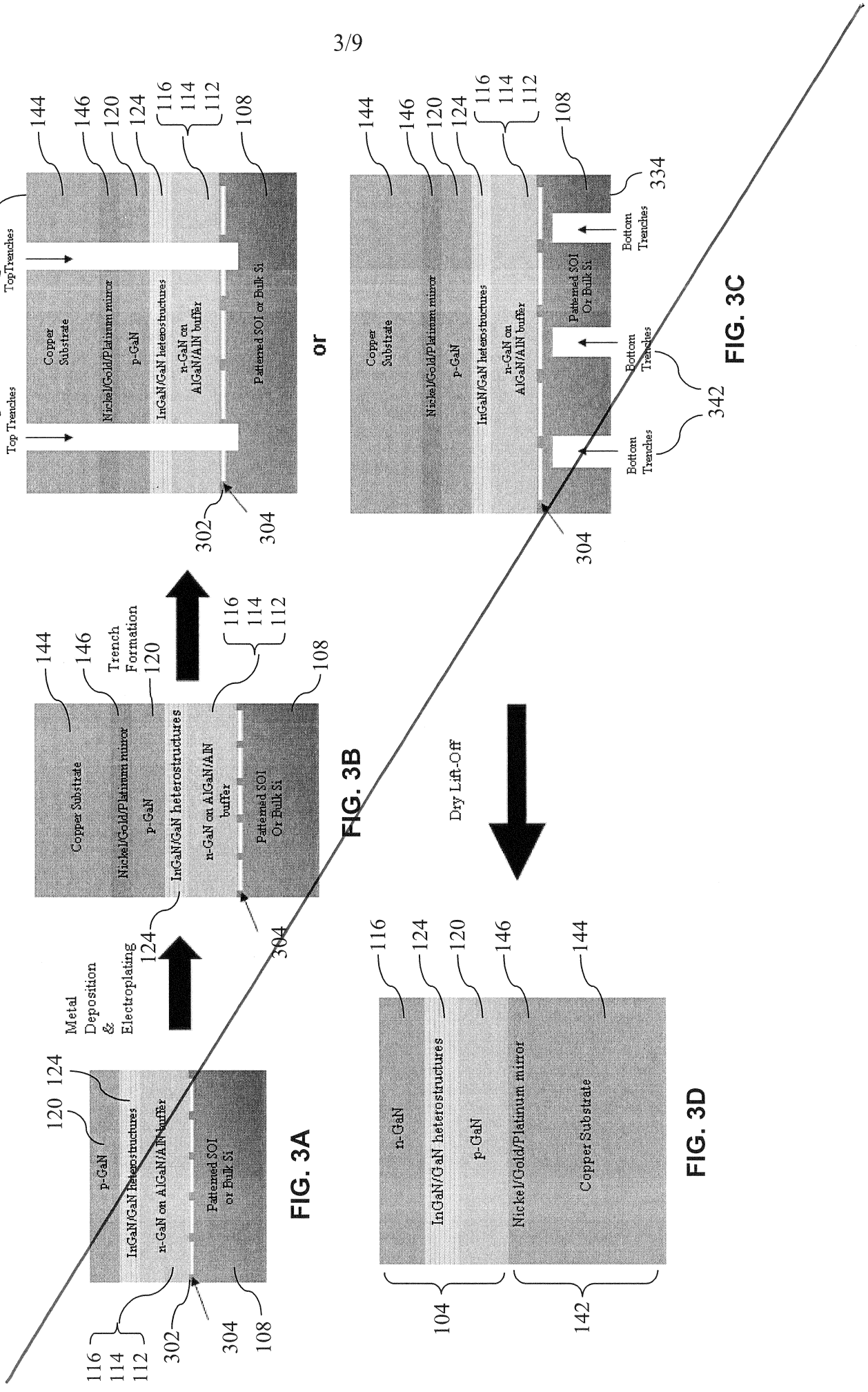


FIG. 3A

FIG. 3B

FIG. 3C

FIG. 3D

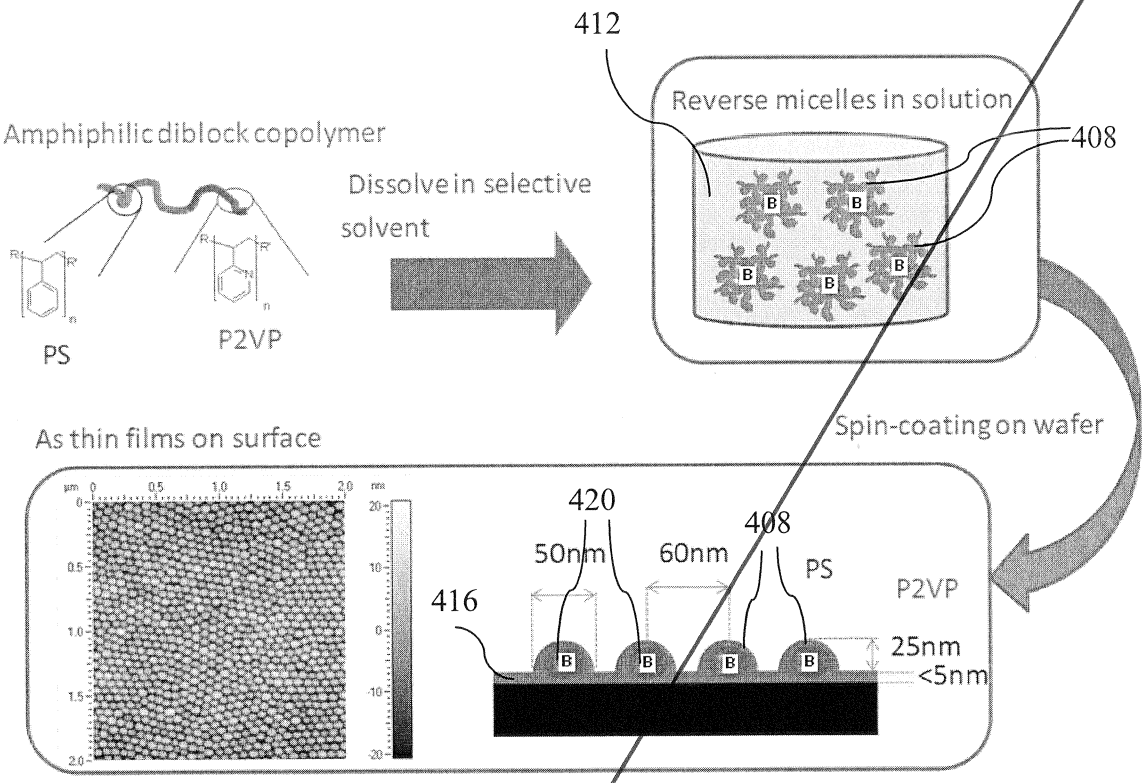

412
Reverse micelles in solution
408
Amphiphilic diblock copolymer
Dissolve in selective solvent
PS
P2VP
Spin-coating on wafer
As thin films on surface
420
408
50nm
60nm
PS
P2VP
416
25nm
<5nm
B

FIG. 4

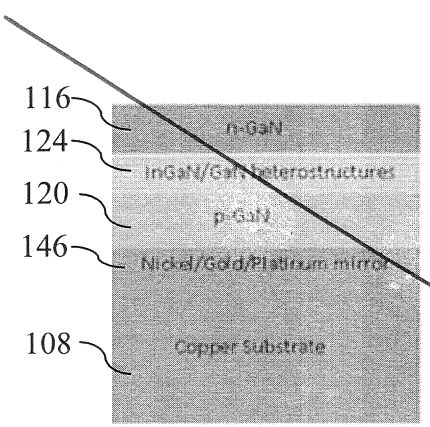


FIG. 5A

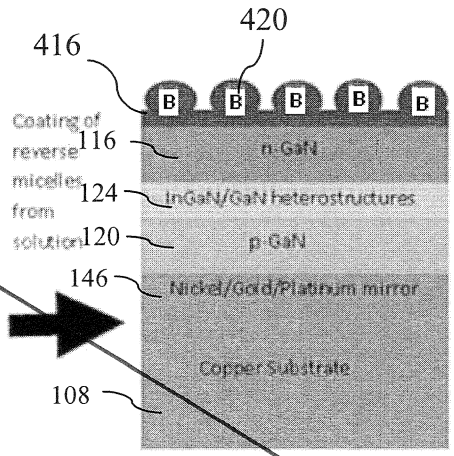


FIG. 5B

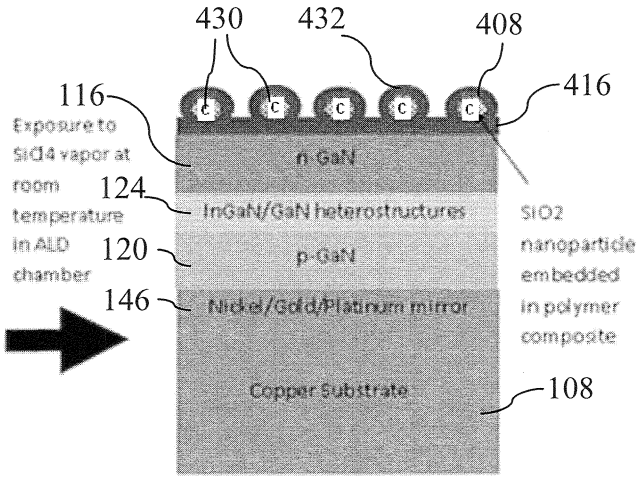


FIG. 5C

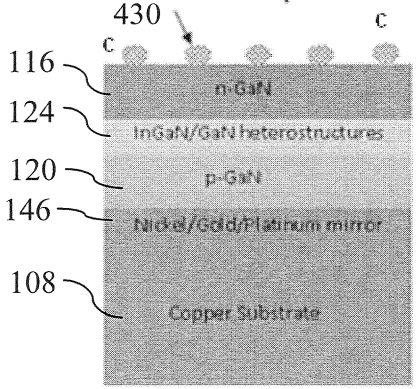


FIG. 5D

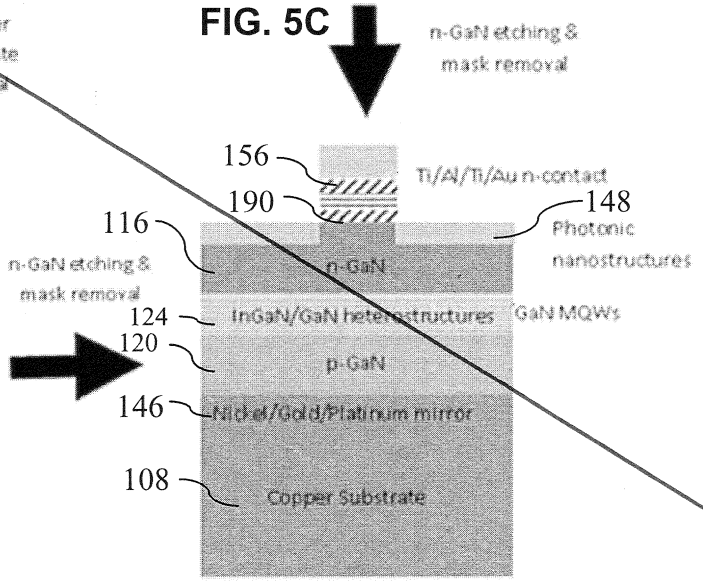
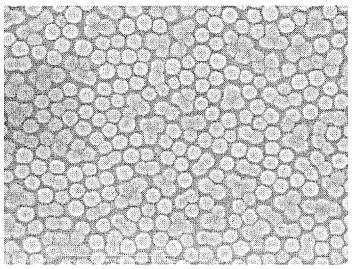
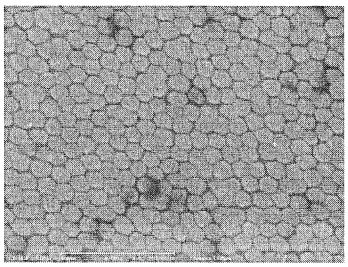


FIG. 5E



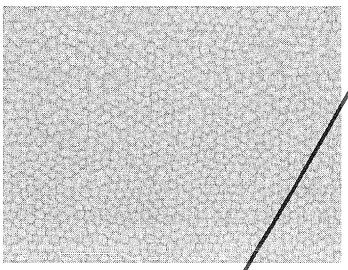
As-deposited

FIG. 6A



10s etch

FIG. 6B



20s etch

FIG. 6C

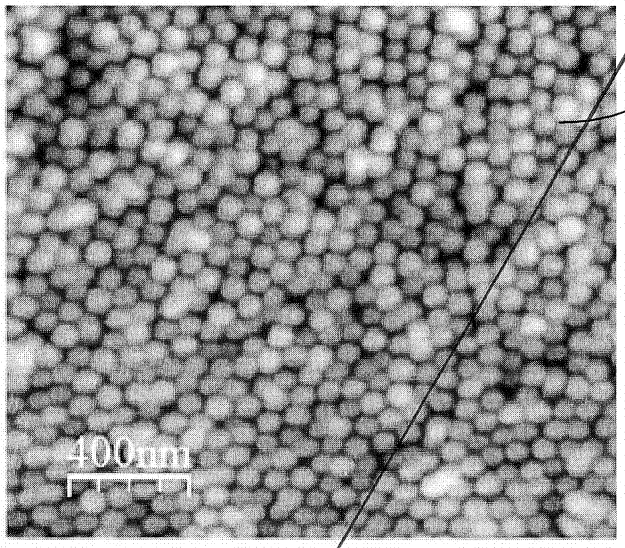


FIG. 7A

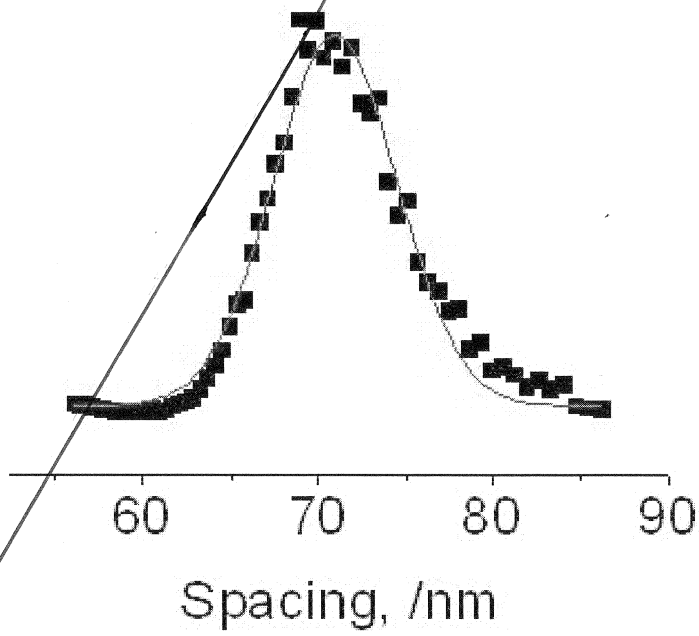


FIG. 7B